

Supporting information

Molecular engineering of Ga-ketoiminates: Synthesis, structure and evaluation as precursors for the additive-free spin-coated deposition of gallium oxide thin films

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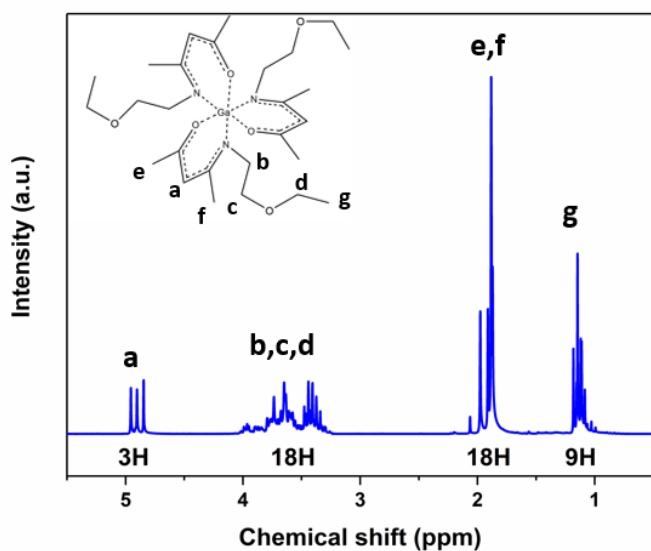


Figure S1. ¹H NMR spectrum of compound [1] – [Ga(eeki)₃].

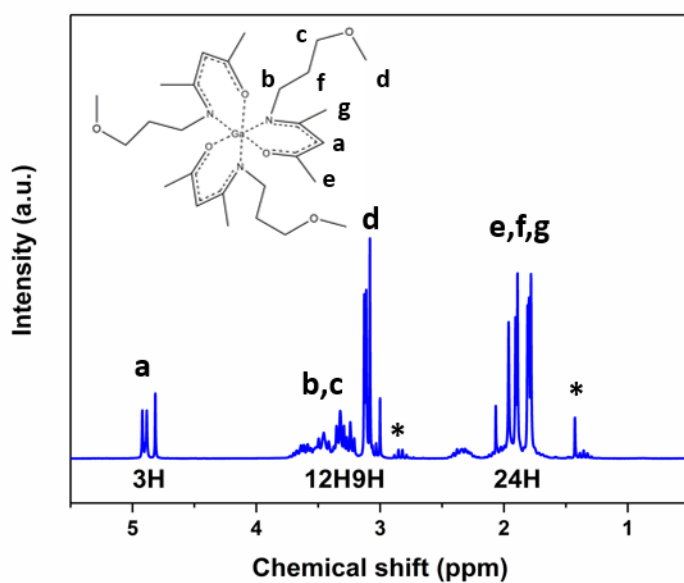


Figure S2. ¹H NMR spectrum of compound [2] – [Ga(mpki)₃]. * = Ligand.

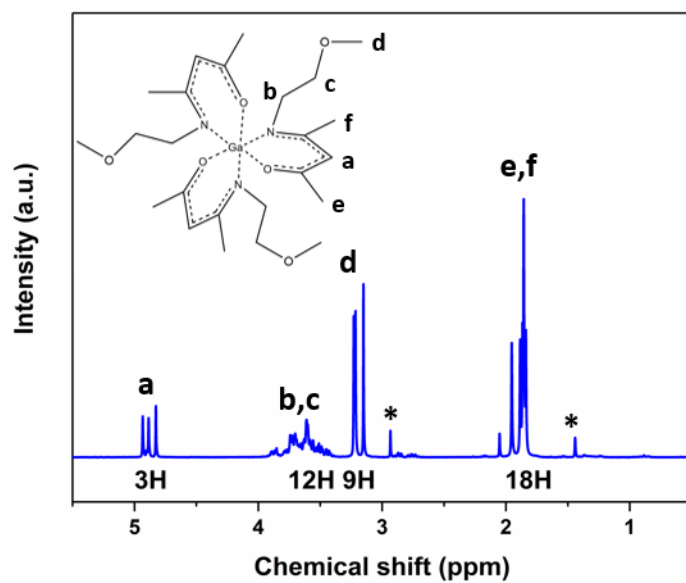


Figure S3. ^1H NMR spectrum of compound [3] – $[\text{Ga}(\text{meki})_3]$. * = Ligand.

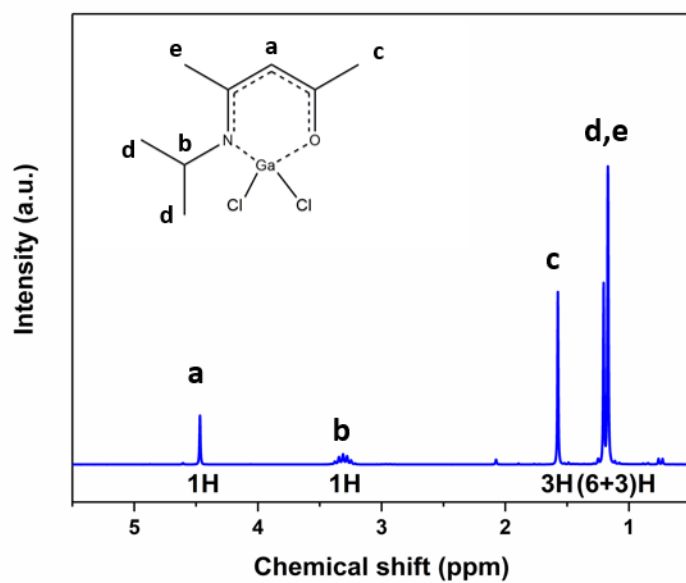


Figure S4. ^1H NMR spectrum of compound [4] – $[\text{Ga}(\text{ipki})\text{Cl}_2]$.

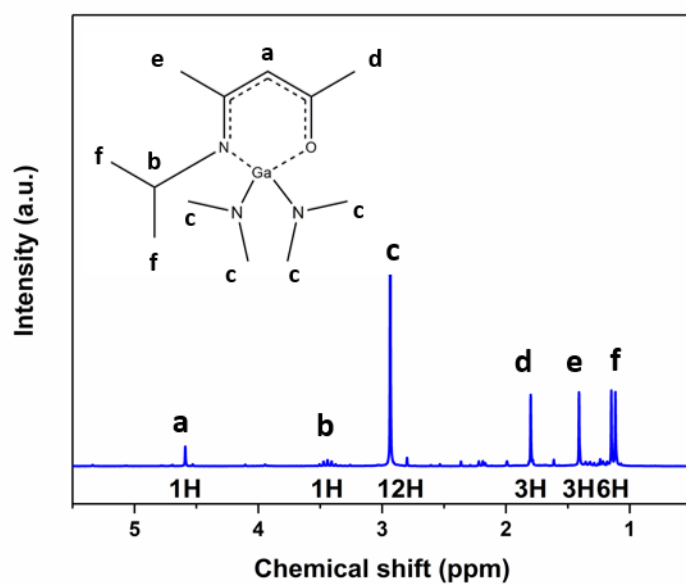


Figure S5. ^1H NMR spectrum of compound [5] – $[\text{Ga}(\text{ipki})(\text{NMe}_2)_2]$.

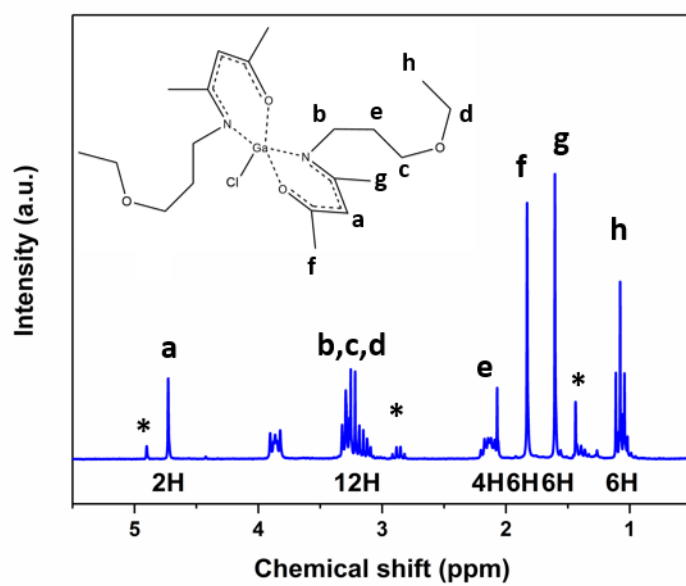


Figure S6. ^1H NMR spectrum of compound [6] – $[\text{Ga}(\text{epki})\text{Cl}_2]$. * = Ligand.

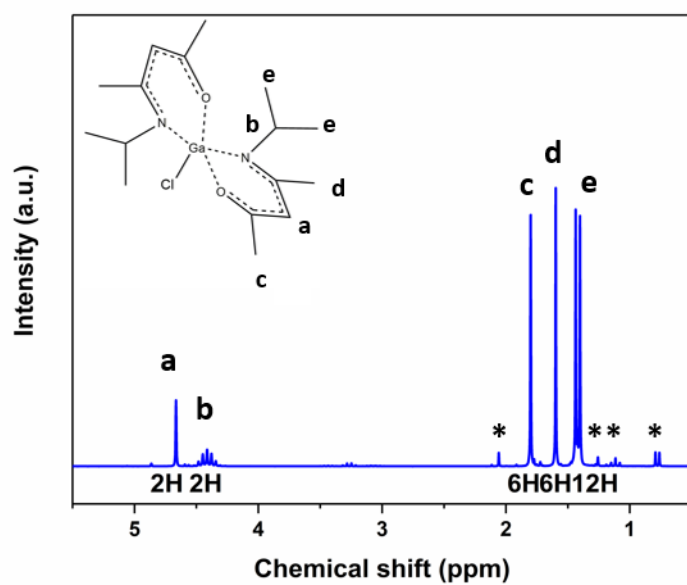


Figure S7. ^1H NMR spectrum of compound [7] - $[\text{Ga}(\text{ipki})_2\text{Cl}]$. * = Ligand

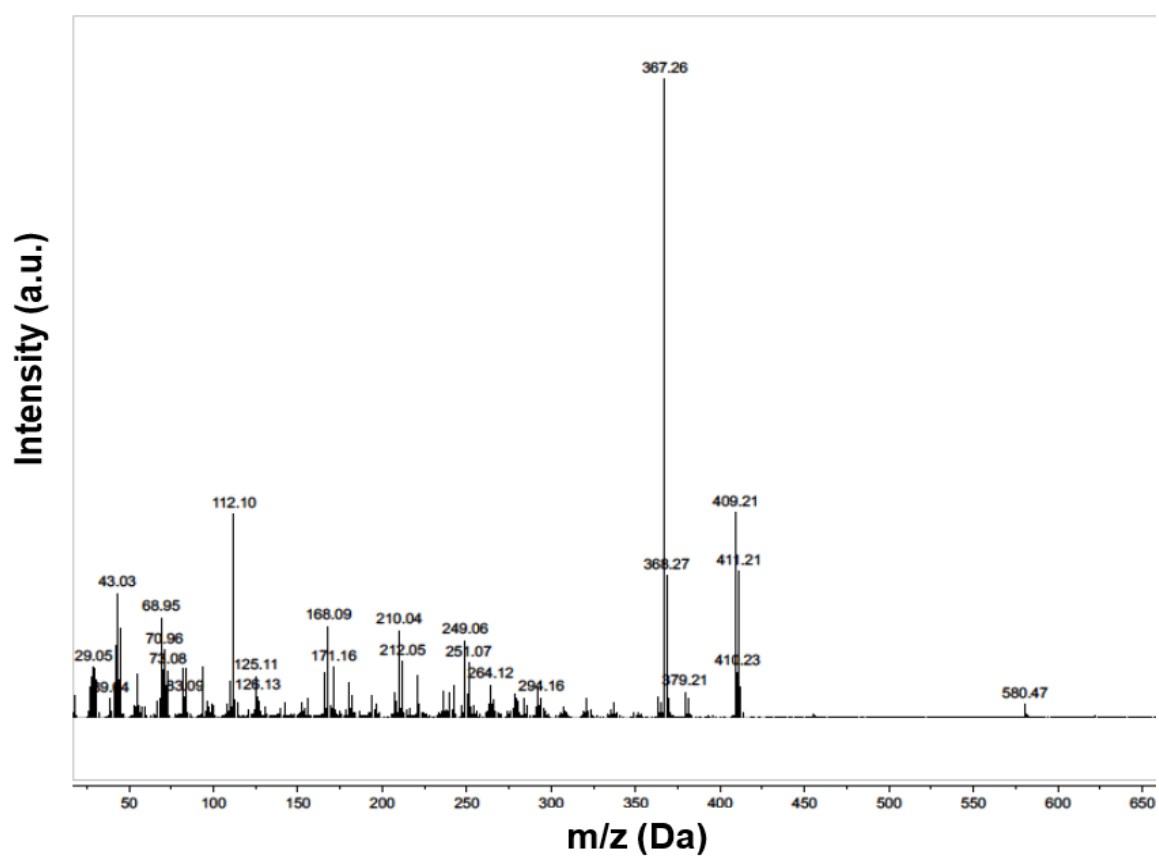


Figure S8. EI-MS spectrum of compound [1].

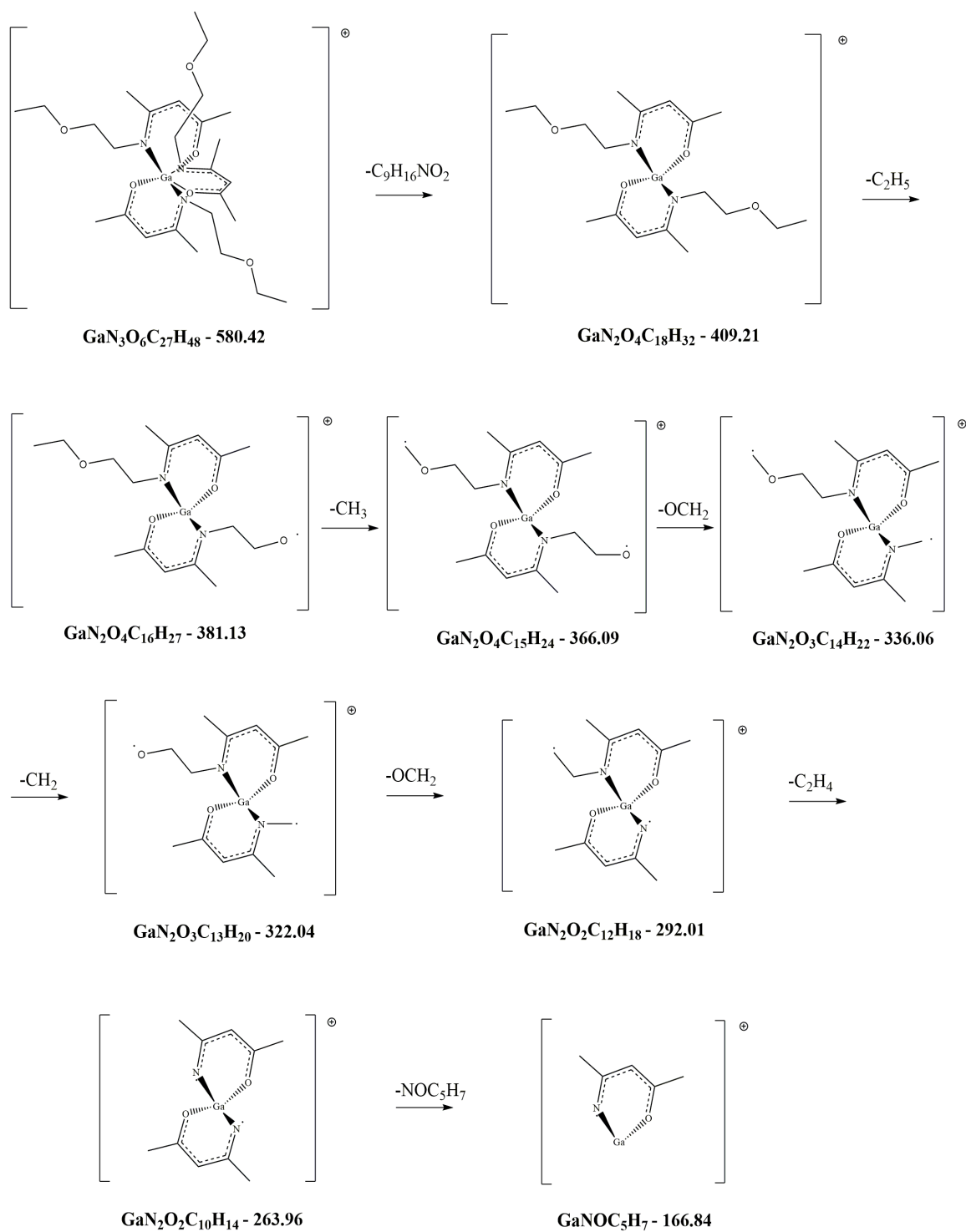


Figure S9. Proposed fragmentation pattern for the EI-MS data in Figure S2

Table S1. Overview of the fragments observed in the EI-MS spectra of compound [4].

Fragments	m / z	Intensity [%]
[M ⁺]	281.0	17.65
[M ⁺ - ·CH ₃]	264.0	100.00
[M ⁺ - ·Cl]	244.0	54.99
[M ⁺ - ·CH ₃ - ·Cl]	228.0	71.23
[M ⁺ - ·CH(CH ₃) ₂ - ·CH ₃]	186.0	9.03
[Ligand ⁺]	140.9	18.66
[M ⁺ - 1x Ligand]	138.9	13.71
[Ga ⁺]	68.9	15.18
[H ₂ CCHCH ₃ ⁺]	42.0	44.92
[H ₂ CCH ⁺]	27.0	14.06

Table S2. Overview of the fragments observed in the EI-MS spectra of compound [5].

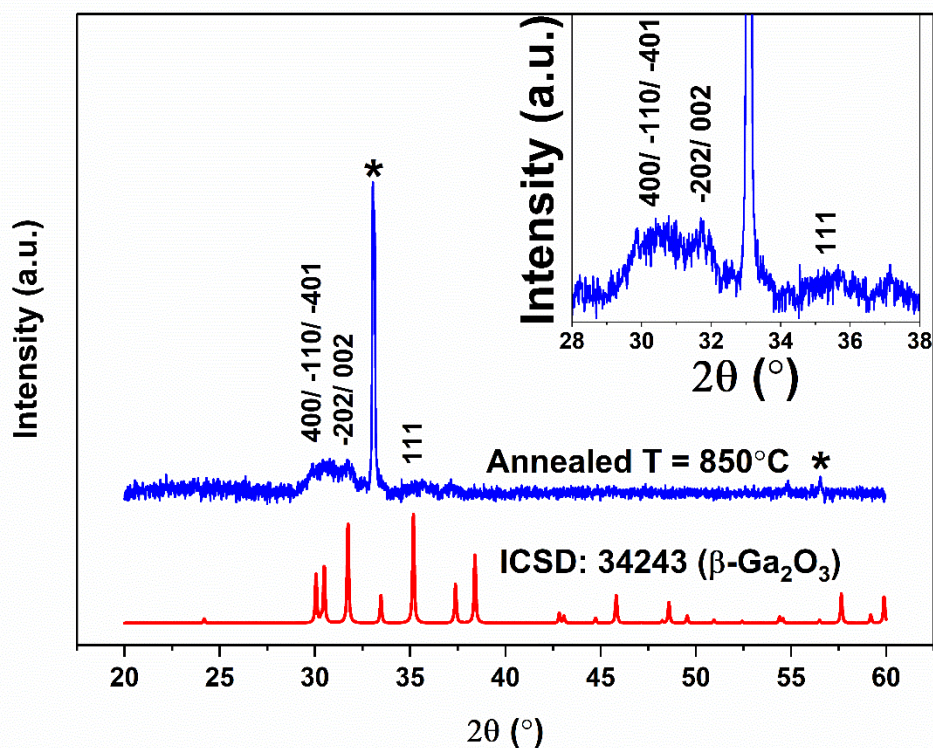
Fragments	m / z	Intensity [%]
[M ⁺]	298.2	1.53
[M ⁺ - N(CH ₃) ₂]	253.1	78.75
[M ⁺ - ·2N(CH ₃) ₂]	209.3	47.40
[M ⁺ - 2N(CH ₃) ₂ - ·2CH ₃]	166.0	1.53
[Ligand ⁺]	140.1	0.78
[Ligand ⁺ - ·CH ₃]	108.1	7.59
[Ligand ⁺ - 2x ·CH ₃]	83.1	7.33
[Ga ⁺]	68.9	48.22
[H ₂ CCHCH ₃ ⁺]	42.0	100.00
[H ₂ CCH ⁺]	27.0	12.04

Table S3. Overview of the fragments observed in the EI-MS spectra of compound [6].

Fragments	m / z	Intensity [%]
[M ⁺]	474.2	1.21
[M ⁺ - ·Cl]	439.2	64.74
[M ⁺ - ·Cl - ·OCH ₂ CH ₃]	395.2	21.46
[M ⁺ - ·Cl - 2CH ₂ CH ₂ OCH ₂ CH ₃]	292.1	6.53
[M ⁺ - ·Cl - 2CH ₂ CH ₂ OCH ₂ CH ₃ - 4CH ₃]	223.1	2.55
[Ligand ⁺]	186.2	18.42
[Ga ⁺]	68.9	3.20
[H ₂ CCHCH ₃ ⁺]	42.0	7.80
[H ₂ CCH ⁺]	27.0	4.41

Table S4. Overview of the fragments observed in the EI-MS spectra of compound [7].

Fragments	m / z	Intensity [%]
[M ⁺]	384.2	26.70
[M ⁺ - ·CH ₃]	371.1	21.46
[M ⁺ - ·Cl]	349.2	90.83
[M ⁺ - ·Cl - 4x ·CH ₃]	291.1	13.66
[M ⁺ - ·Cl - 3x ·CH ₃ - ·CH(CH ₃) ₂]	264.1	26.77
[M ⁺ - ·Cl - 4x ·CH ₃ - ·CH(CH ₃) ₂]	249.1	22.47
[M ⁺ - 1x Ligand]	244.0	100.00
[M ⁺ - 1x Ligand - ·CH ₃]	228.0	18.54
[M ⁺ - 1x Ligand - ·OCCH ₃]	202.0	35.37
[Ligand ⁺]	140.1	68.12
[Ligand ⁺ - ·CH ₃]	126.1	23.61
[Ligand ⁺ - 2x ·CH ₃]	108.1	18.36
[Ligand ⁺ - ·CH ₃ - ·CH(CH ₃) ₂]	83.1	24.84
[Ga ⁺]	68.9	33.00
[H ₂ CCHCH ₃ ⁺]	42.0	73.07
[H ₂ CCH ⁺]	27.0	21.51

**Figure S10.** XRD pattern of the gallium oxide thin film from a process deposited on Si(100) using compound [1] with 25 spin coating cycles at a hotplate temperature of 350 °C after an annealing at 850 °C for 2 h under ambient conditions. The β-gallium oxide reference pattern in red corresponds to the ICSD no. 34243. The Inset shows a close up of the obtained reflexes. * = silicon substrate.

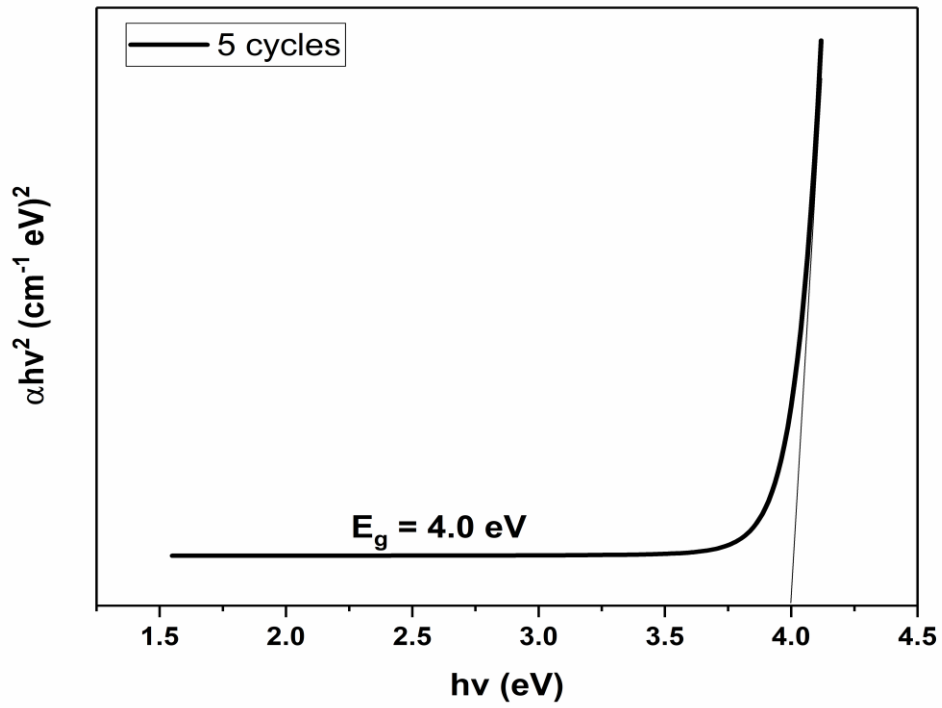


Figure S11. Tauc plot derived from the transmittance data of the sample deposited with 5 spin-cycles.

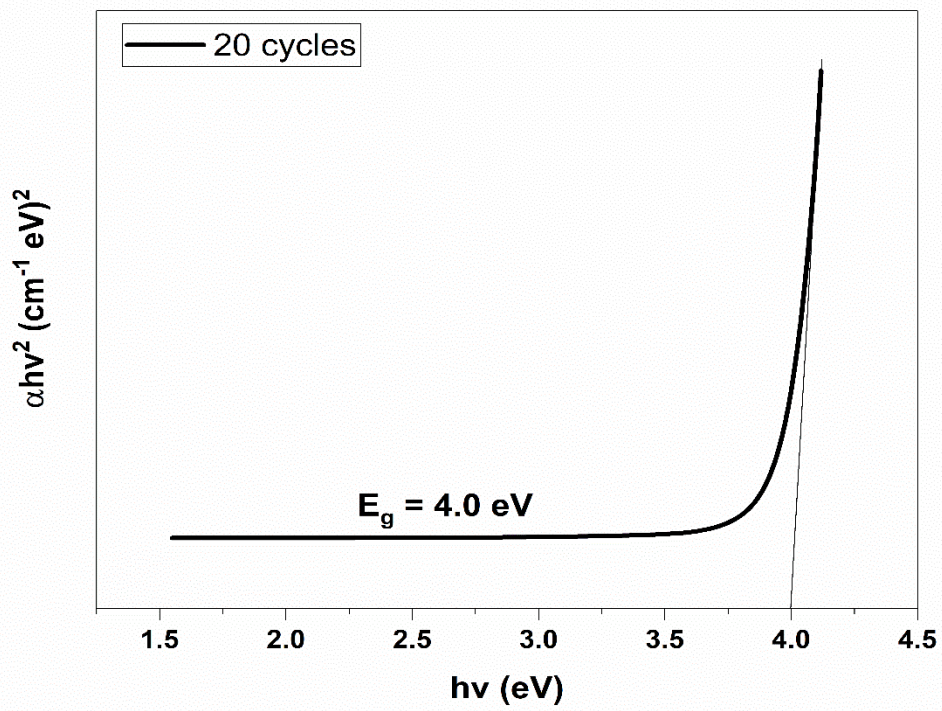


Figure S12. Tauc plot derived from the transmittance data of the sample deposited with 20 spin-cycles.

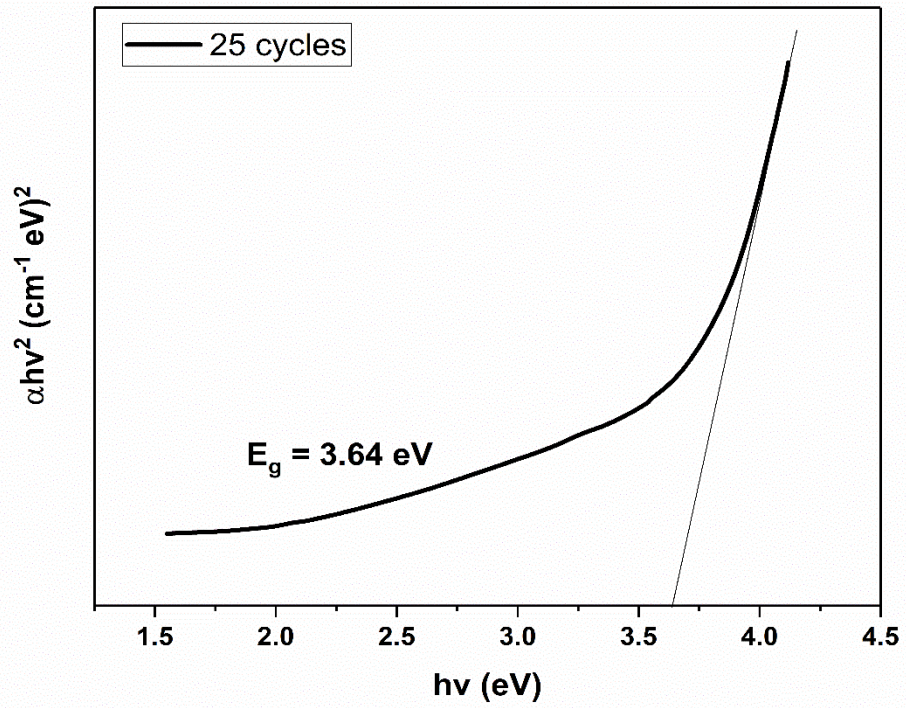


Figure S13. Tauc plot derived from the transmittance data of the sample deposited with 25 spin-cycles